

Supplementary Materials:

**Comparative Study of Thermal and Plasma-Enhanced
Atomic Layer Deposition of Iron Oxide Using
Bis(*N,N'*-di-butylacetamidinato)iron(II)**

Boyun Choi [†], Gun-Woo Park [†], Jong-Ryul Jeong and Nari Jeon ^{*}

Department of Materials Science and Engineering, Chungnam National University,
Daejeon 34134, Republic of Korea; bow06123@o.cnu.ac.kr (B.C.);
adgv9073@gmail.com (G.-W.P.); jrjeong@cnu.ac.kr (J.-R.J.)

^{*} Correspondence: njeon@cnu.ac.kr

[†] These authors contributed equally to this work.

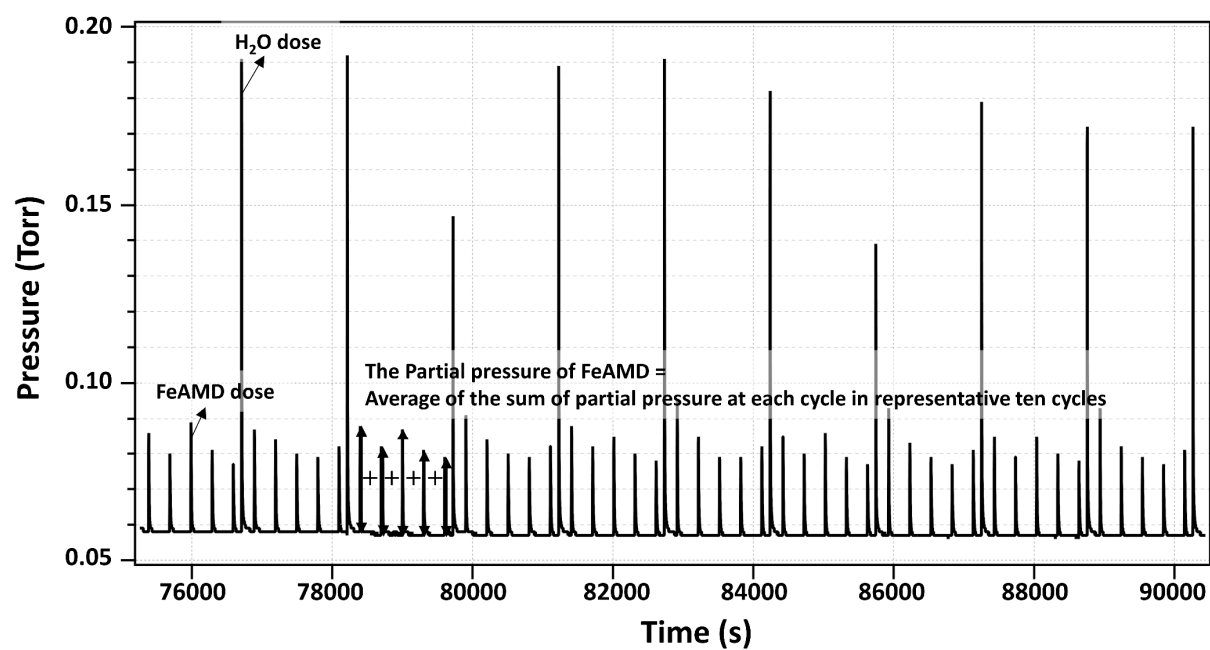


Figure S1. An example of the pressure log collected during the FeAMD half-cycle, in which the FeAMD dose was repeated five times. In this log, the partial pressure of FeAMD was recorded as 128 mTorr.

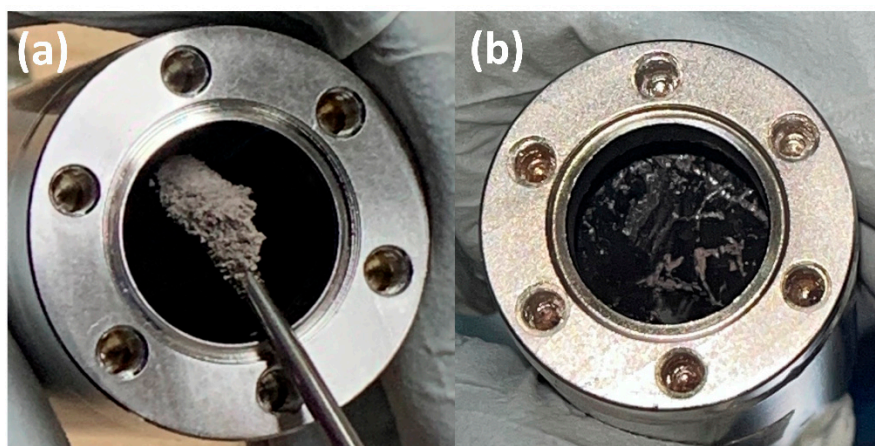


Figure S2. Pictures of FeAMD precursor of **(a)** an as-received state, and **(b)** an agglomerated state.

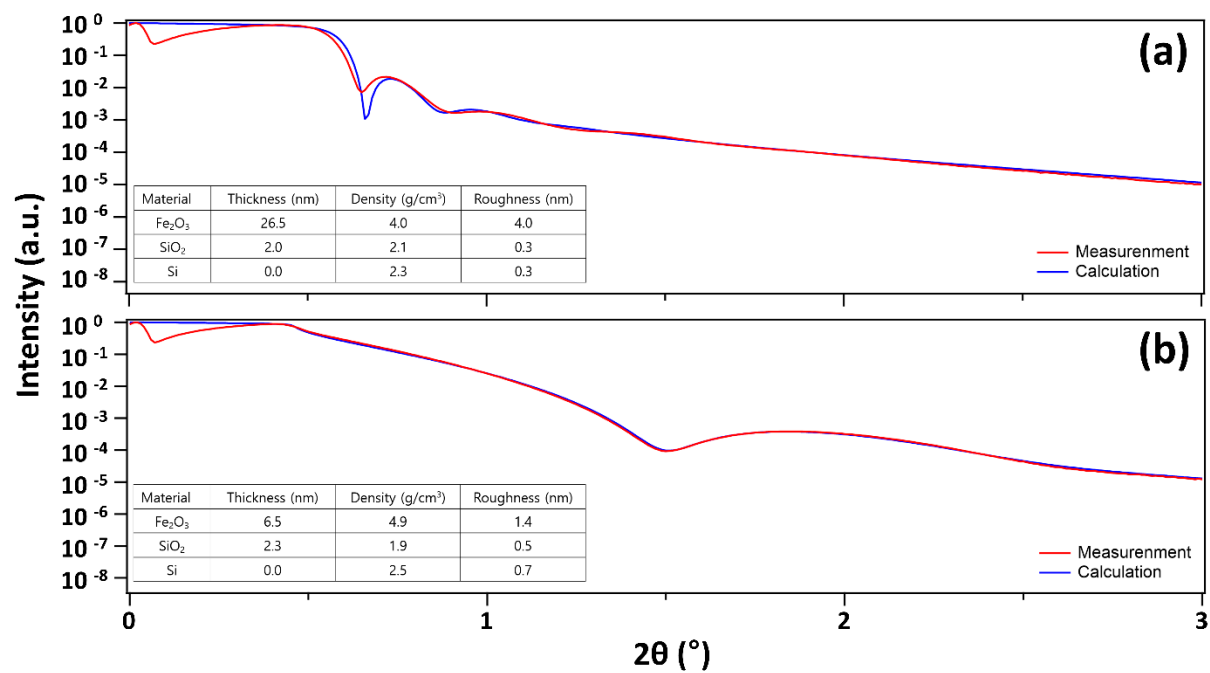


Figure S3. X-ray reflectivity spectra of **(a)** thermal ALD and **(b)** PEALD films.

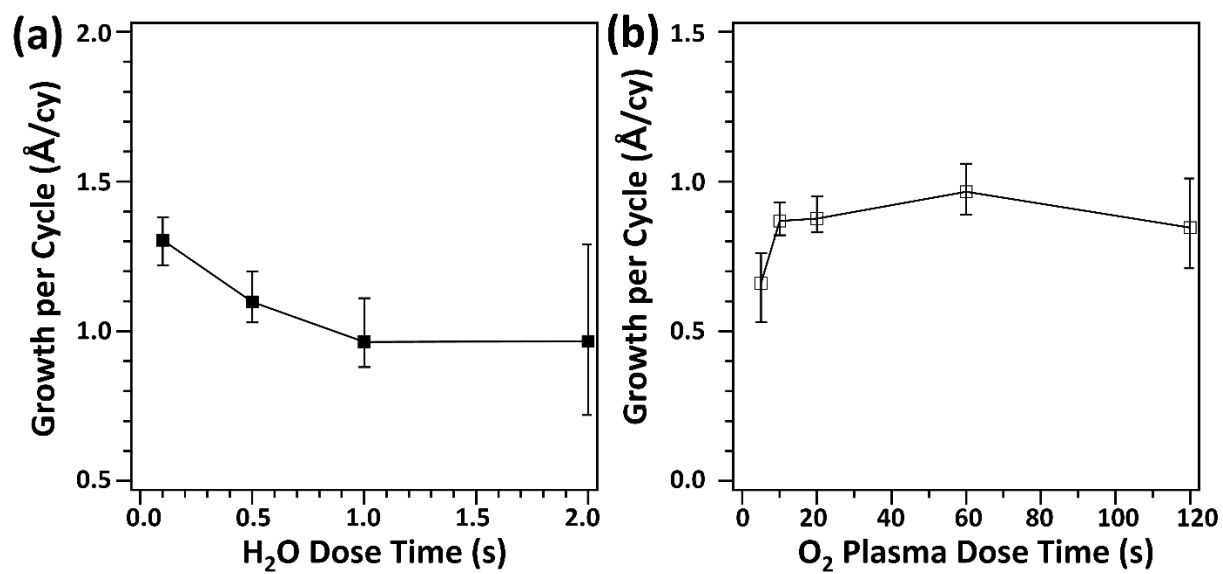


Figure S4. GPC of FeO_x films as a function of (a) H_2O dose time (thermal ALD) and (b) O_2 plasma time (PEALD).

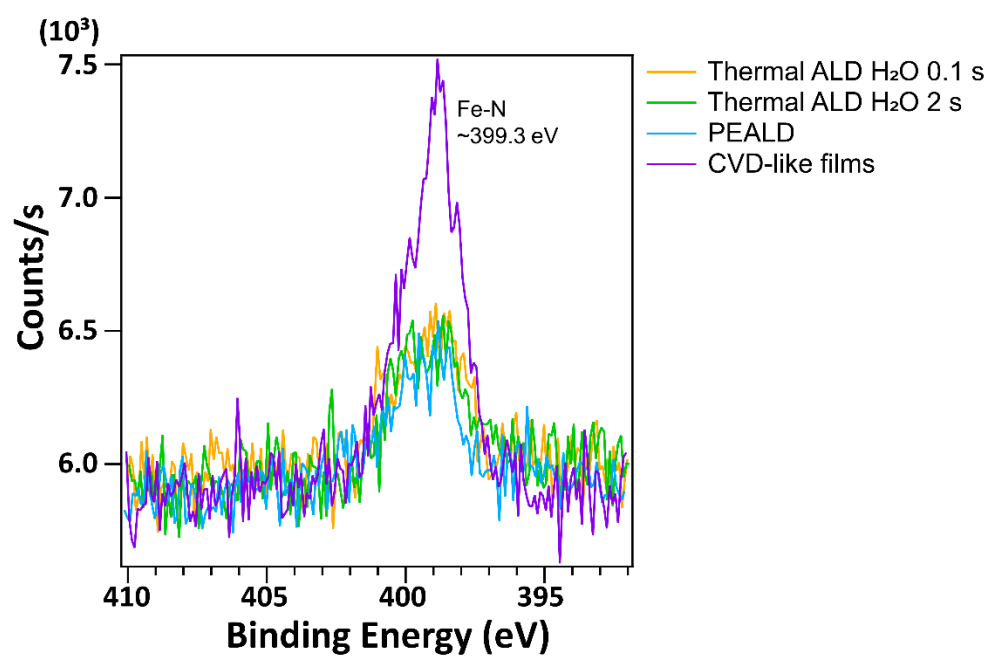


Figure S5. N 1s HRXPS of the thermal ALD, PEALD, and CVD-like films.